



Appl. No.: 10/027,282
Reply to Office Action of: 12/02/2004

1731

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : 10/027,282
Applicant : House, Keith L, et al.
Filed : 12/21/2001
Title : Plasma Chemical Vapor Deposition Methods And Apparatus

TC/A.U. : 1731
Examiner : Hoffmann, John M

Docket No. : SP01-347

Mail Stop: Amendments
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING (37 CFR 1.8a)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Mail Stop: Amendments, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on: 12/16/04

[Handwritten signature]
Kevin M. Able

AMENDMENT

Sir:

In response to the Office action of December 2, 2004, please amend the above-identified as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 5 of this paper.